

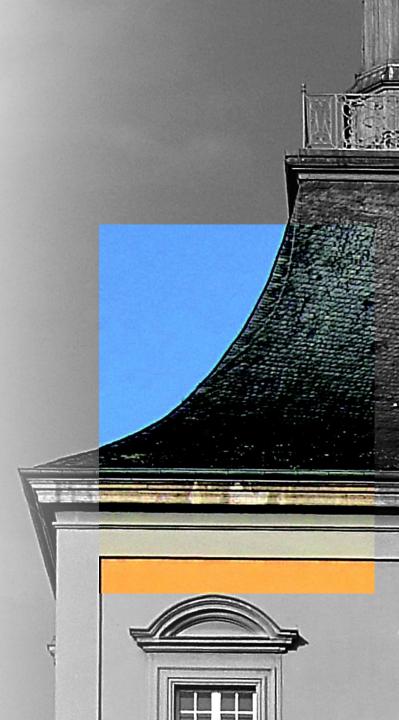
# Radiation hardness and development of a large electrode DMAPS design in a 150 nm CMOS process.

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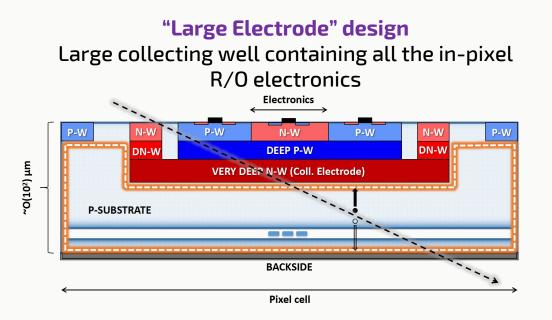
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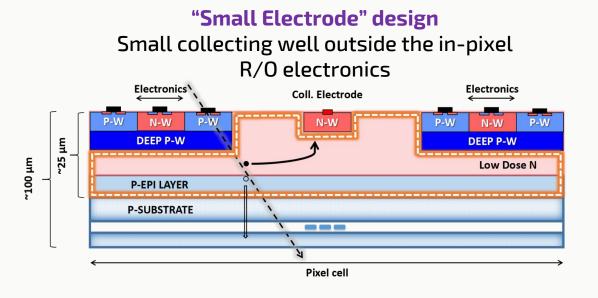
# DEPLETED MONOLITHIC ACTIVE PIXEL SENSORS (DMAPS)

Commercial CMOS process (multiple wells for shielding), no hybridization, considerable depleted regions in highly resistive substrates, fast charge collection by drift.



**PROS:** Short drift distances, strong E-field (Rad-hard). **CONS:** Large sensor capacitance, high analog power.

---> Requires design efforts to optimize timing and minimize cross-coupling into the collection node.



**PROS:** Small sensor capacitance, low power and noise. **CONS:** Weak electrical field compromises rad-hardness.

---> Requires process modifications and small pixel pitch to optimize charge collection.





### **DMAPS FOR HIGH ENERGY COLLIDER EXPERIMENTS**

#### **Requirements of future HEP experiments:**

	ITk Outer Layer	BELLE 2 Upgrade
Occupancy	1 MHz/mm <sup>2</sup>	1.5 MHz/mm <sup>2</sup>
Time Res.	<b>25 ns</b>	0(100) ns
NIEL	10 <sup>15</sup> n <sub>eq</sub> /cm <sup>2</sup>	10 <sup>14</sup> n <sub>eq</sub> /cm <sup>2</sup>
TID	80 Mrad	100 Mrad
Area	<b>O(10m<sup>2</sup>)</b>	<b>O(3m<sup>2</sup>)</b>

#### **DMAPS** would offer:

- Reduced material budget compared to hybrids.
- Cheaper and less complex module production.

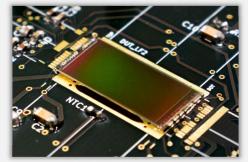
#### The Monopix DMAPS developments

Column-Drain ("FE-I3 like") synchronous R/O architecture and fast front-end implementations

Design optimization to preserve charge collection after irradiation

#### **LF-Monopix:** Large electrode DMAPS in LFoundry 150 nm CMOS

**TJ-Monopix:** Small electrode DMAPS in Tower 180 nm CMOS



(This talk)

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(Next talk by C. Bespin)



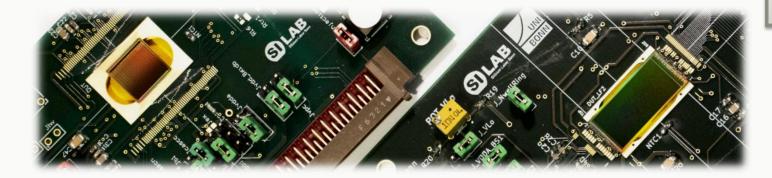


### **THE LF-MONOPIX PROTOTYPES**

- Full-size (~cm<sup>2</sup>) large electrode DMAPS.
- Functional columndrain R/O architecture.
- In-pixel electronics in >2 kOhm-cm resistive substrates.

LF-Monopix1 (Mar 2017)

LF-Monopix2 (Feb 2021)

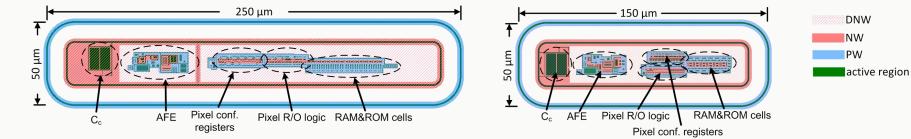


LFoundry 150 nm CMOS process





Pixel layouts (Top view):



DAQ system: Bonn's Multi-I/O 3 ("MIO3") and General Purpose Analog Card ("GPAC")







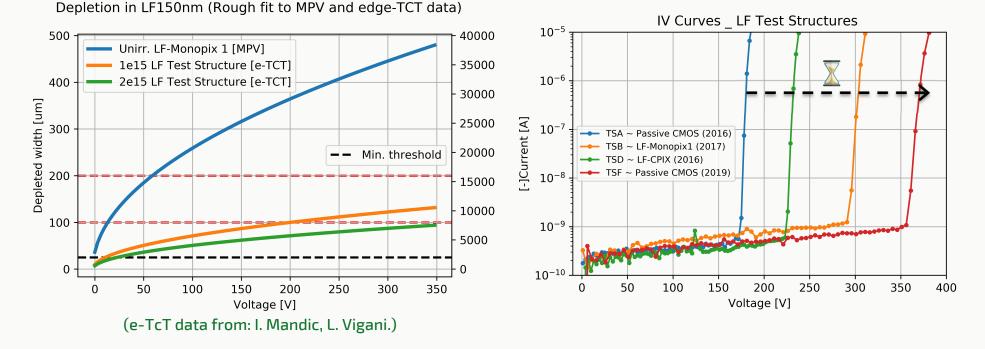
### **DEPLETION IN LFOUNDRY HR-SUBSTRATES**

CMOS DMAPS aim to deplete the silicon bulk and collect charge mainly by drift

In order to do so, the **LF-Monopix** chips use:

- A highly resistive substrate:
- ~7 kOhm-cm, Czochralski processed

• Large reverse bias voltages: Improved across LF150 prototypes

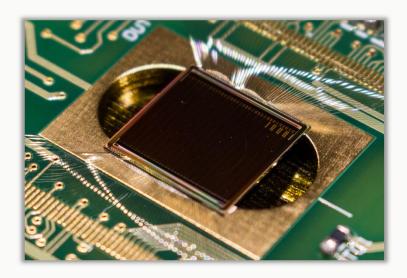






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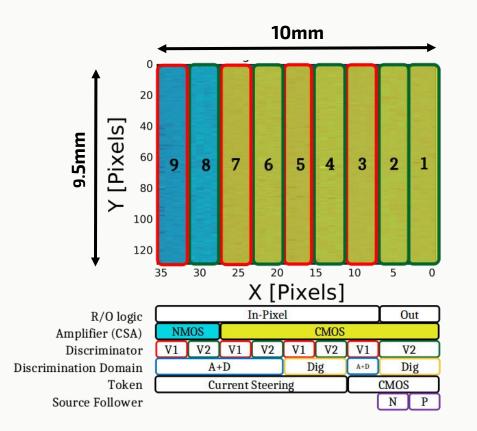
### **LF-MONOPIX1**



- Functional in-pixel R/O logic.
- Large 50 x 250 μm<sup>2</sup> pixel array (129 rows x 36 cols)
- Bunch-crossing clock frequency (40MHz clock)
- 40 MHz/160MHz CMOS or LVDS serial output.
- Timestamping: 8-bit LE/TE (ToT) @ 25 ns.
- Power: 55 µW/pixel (~1.7W/cm<sup>2</sup>)

#### Noise: ~150-200e-

#### Tuned Thr: ~1600 ± 100e-



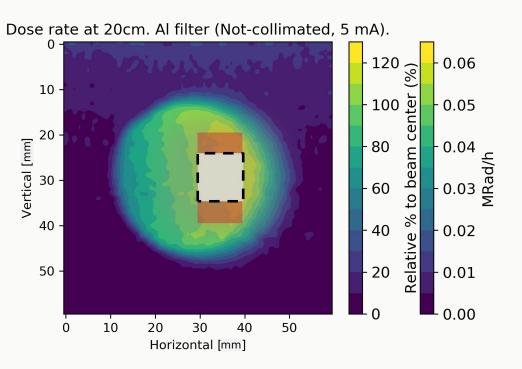






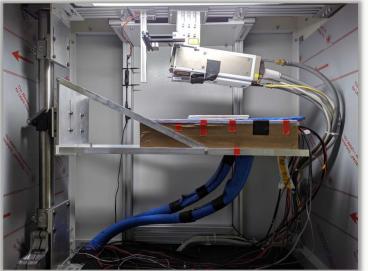


### TID IRRADIATION @ SILAB BONN



- **Sample:** 100 um thick LF-Monopix1 (Powered on)
- X-ray tube settings: 40 kV, 50 mA ---> 0.6 MRad/h
- **Temperature:** Cooled down with chiller through plate. **0**±**2 C** in **NTC**
- 15 steps up to 100 MRad

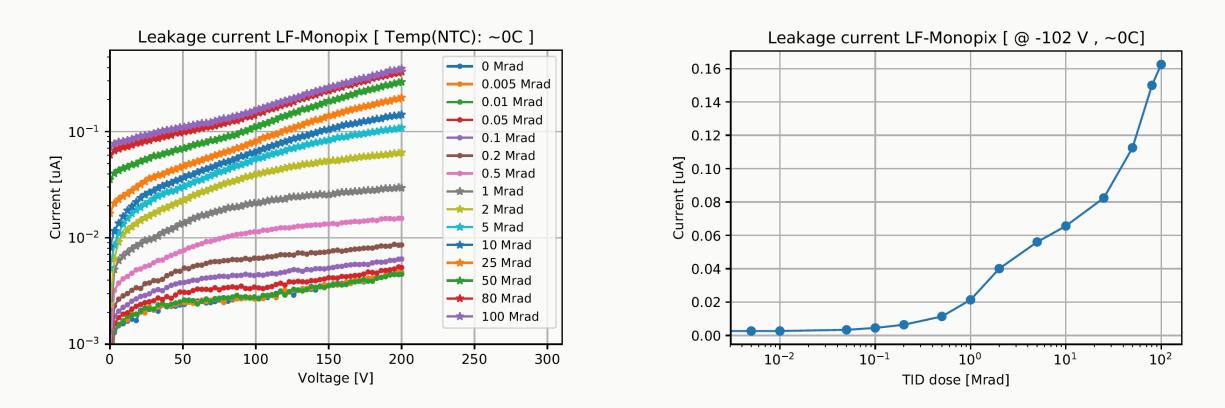








### **TID IRRADIATION: LEAKAGE CURRENT**



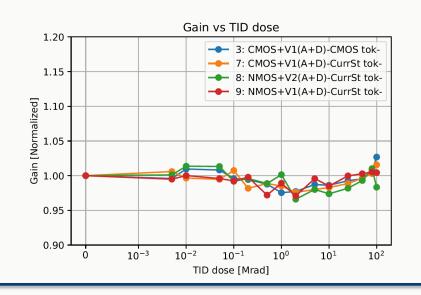
#### Increase of 2 orders of magnitude after 100 Mrad at 0 ± 2C temperature



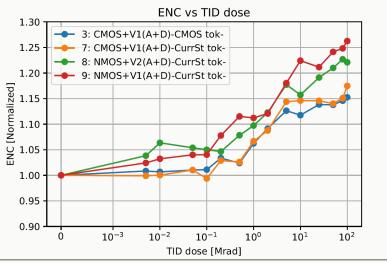


### **TID IRRADIATION: GAIN & ENC**

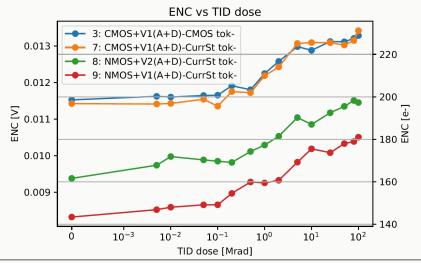
• **Relative Gain variation:** <3%



• **Relative ENC increase:** NMOS (25%) > CMOS (15%)







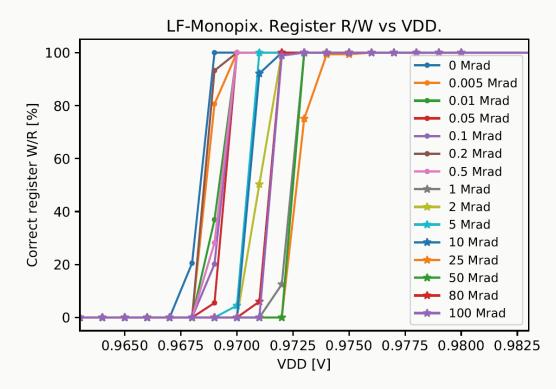




### **TID: DIGITAL PERFORMANCE**

### • Shift register R/W:

Variation < 0.5% in whole matrix



#### No degradation of digital performance.



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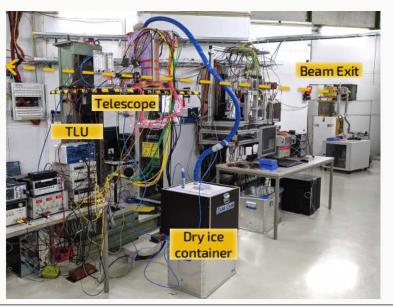


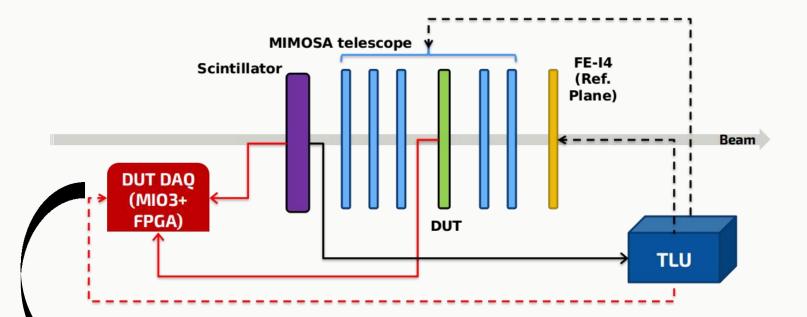
### TB DATA ACQUISITION AND SAMPLING @ DESY

#### **Telescope setup:**

- 1 LF-Monopix1 DUT (200/100 um thickness),
- 5 MIMOSA26 tracking planes
- 1 FE-I4 timing reference plane.
- Triggered by a plastic scintillator through a TLU.

Beam: 5 GeV e- at DESY TB21





Scintillator, TLU and DUT (Token) timestamps sampled with a **640 MHz** clock in the MIO3 FPGA.

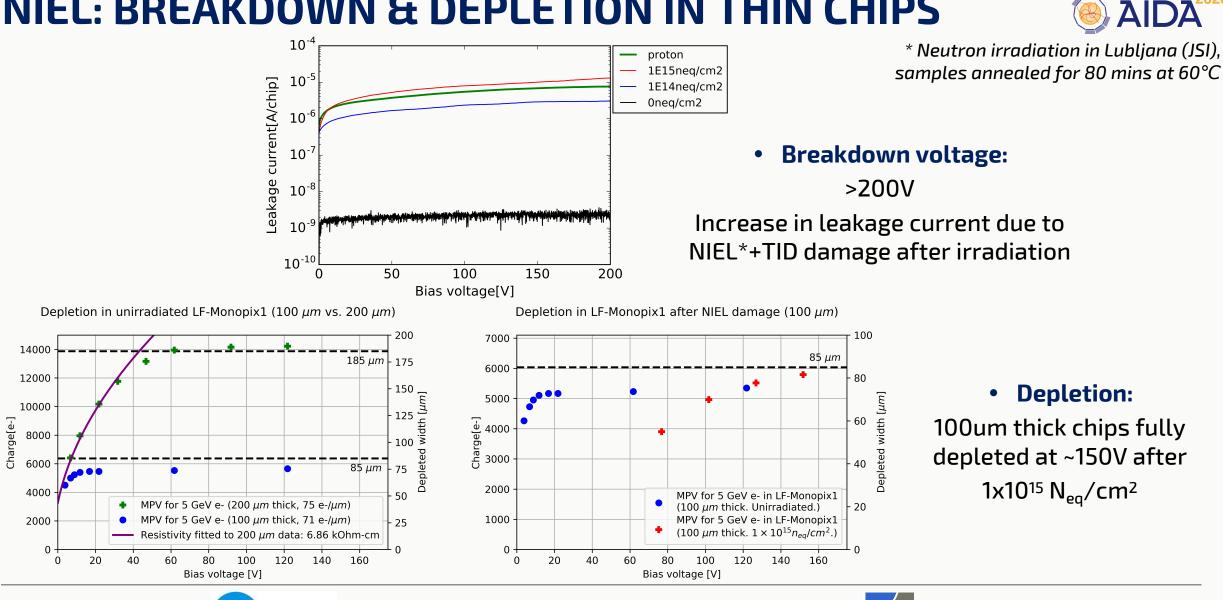
TB data analysis carried out using: https://github.com/SiLab-Bonn/beam\_telescope\_analysis







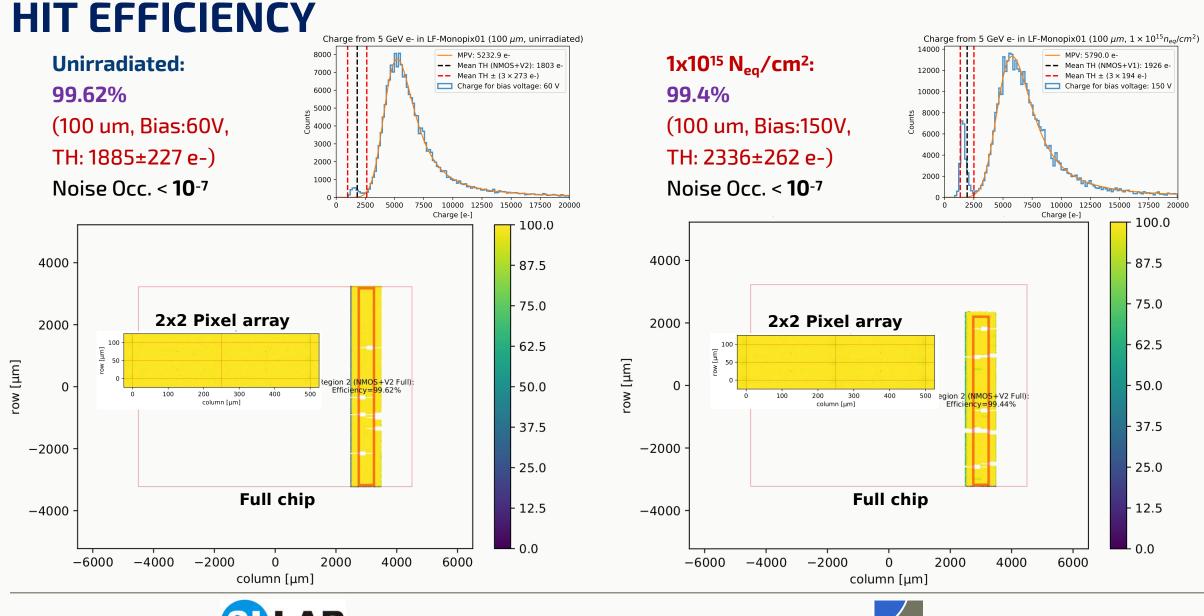
### **NIEL: BREAKDOWN & DEPLETION IN THIN CHIPS**









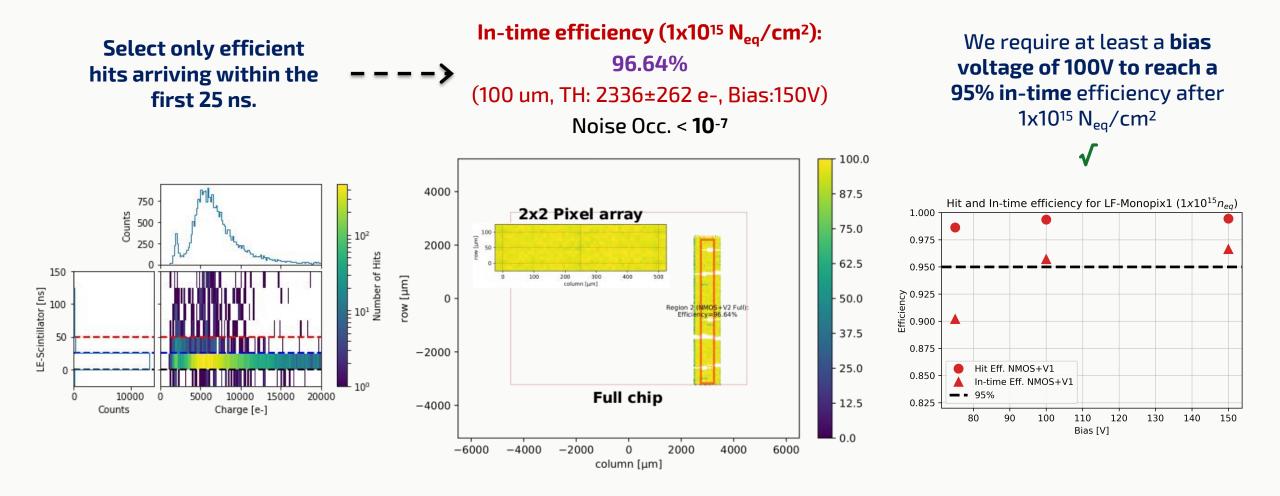


BONN

Silizium Labor Bonn



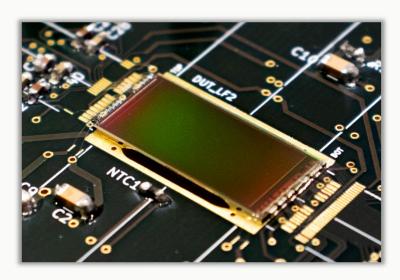
### **IN-TIME EFFICIENCY**



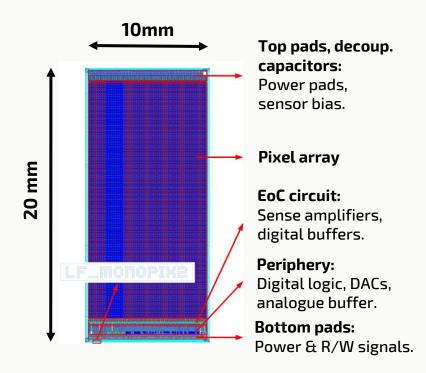




### LF-MONOPIX2



- Smaller pixel pitch than LF-M1: 50 x 150  $\mu m^2$ 
  - → Reduced C<sub>det</sub>
    (ergo: lower noise & power)
    → Larger pixel array
    (340 rows x 56 cols)
- 40 MHz/160MHz CMOS or LVDS serial output.
- Timestamping: 6-bit LE/TE (ToT) @ 25 ns.
- Power: ~30 µW/pixel
- Injection & HitOr: Digital, at pixel level.



### Rad-hard:

Optimized LF-Monopix1 front-end with best timing and performance after NIEL and TID irradiation.

 $\checkmark$ 

Improved pixel layout for **further cross-coupling mitigation** 

 $\checkmark$ 



Column-drain R/O in

a **2 centimeter long** 

column, with full in-

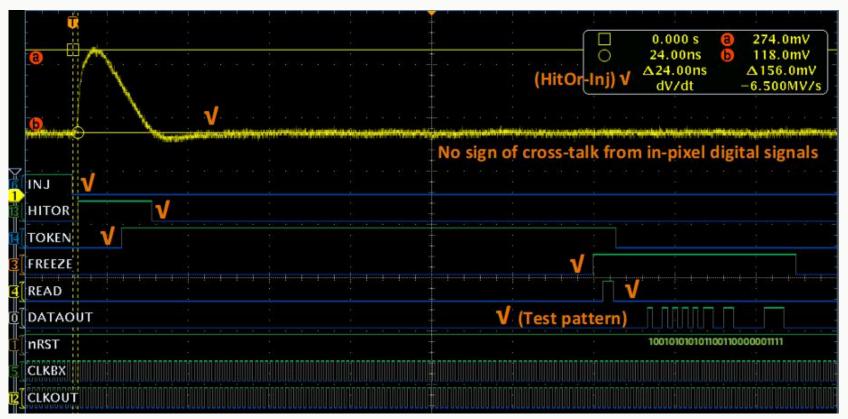
pixel electronics.

 $\checkmark$ 

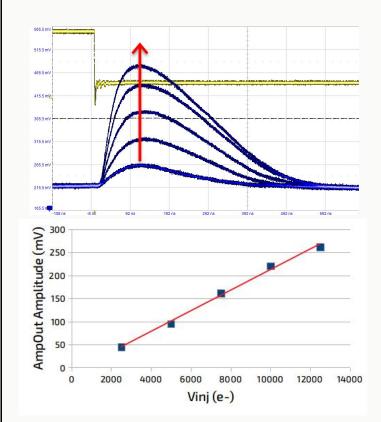


# FUNCTIONAL ANALOG MONITOR, R/O AND INJECTION

• Correct R/O architecture operation and data output.



• Linear CSA response.



Injection of 1V pulse to a single pixel - 40 MHz R/O enabled

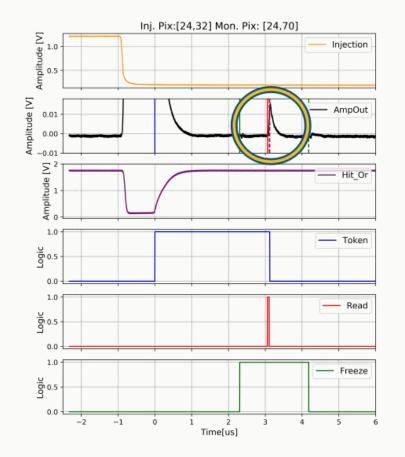
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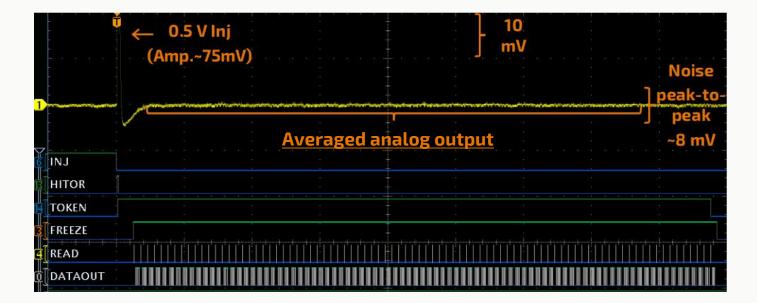


## **ENHANCED CROSS-COUPLING MITIGATION**

• In LF-M1: Small coupling signal coincident with switching of READ in R/O



• <u>In LF-M2</u>, after improved pixel layout based on observations in LF-M1:



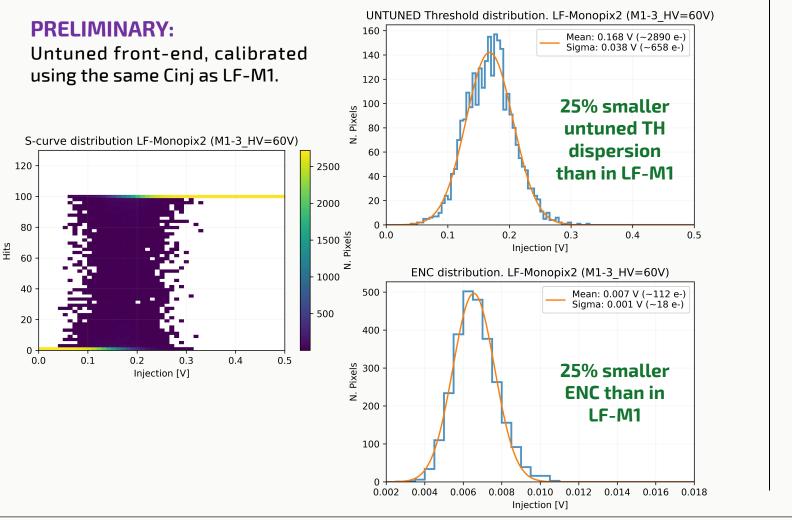
No sign of any coupling coincident with R/O digital switching while carrying signals from pixels across the column



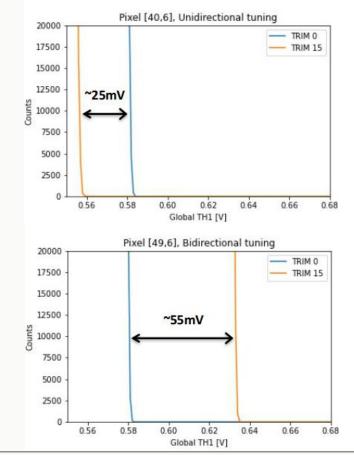




### **DEFAULT FRONT-END PERFORMANCE**



New Bi-directional polarization of the discriminator: Larger tuning range for the same LSB current in LF-M2.

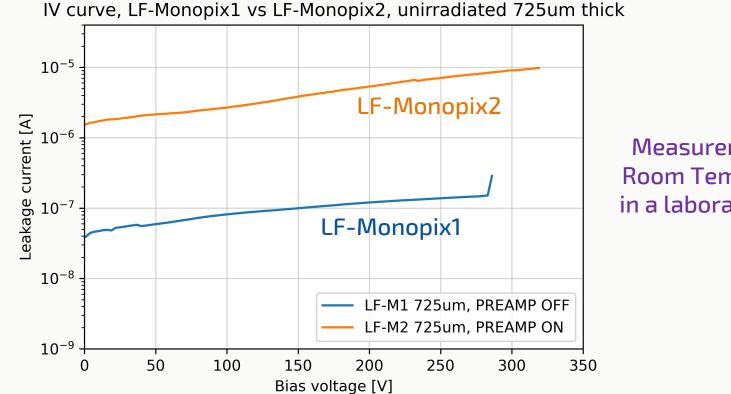






### **BREAKDOWN IN LF-MONOPIX2**

Breakdown voltage improved from LF-Monopix 1 to LF-Monopix2: >320V •



Measurements at Room Temperature in a laboratory desk





### CONCLUSIONS

- Fully functional fast R/O architecture in large electrode DMAPS chips designed in a 150nm CMOS process on highly resistive wafers.
- X-ray irradiation and test beam measurements have demonstrated that <u>the LF-Monopix</u> prototypes are radiation-hard:
  - Small analog and digital degradation after 100 MRad TID dose
  - Full depletion of thinned sensors after neutron fluences of  $1 \times 10^{15} N_{eq}/cm^2$
  - Hit efficiency after  $1 \times 10^{15} \text{ N}_{eq}/\text{cm}^2 > 99\%$
  - In-time efficiency after  $1 \times 10^{15} N_{eq}/cm^2 > 96\%$
- An updated long-column design ("LF-Monopix2") with smaller pixel size is back from submission and it is fully functional.
- Design efforts towards improved cross-coupling mitigation and front-end performance on LF-Monopix2 are promising.







### Thanks.

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